

Workshop I : Extreme Ultraviolet Technology and Applications Workshop

Chairs: Pin-Jiun Wu (吳品鈞)/ Bor-Yuan Shew (許博淵)/ Mau-Tsu Tang (湯茂竹)

September 4 (Thursday)

Place: M222/M223

08:30 Registration -@Activity Center (Entrance 5)

09:00 **SIKA 十週年 -- ACNS and NSRRC Remote Celebration**
Place: D260

10:30 **Opening Remarks**

Chia-Hung Hsu (徐嘉鴻), NSRRC (國家同步輻射研究中心)

Session Chair: Bor-Yuan Shew (許博淵)

10:40 I1 **Lensless EUV Lithography and Metrology at Swiss Light Source**

Yasin Ekinci, Paul Scherrer Institute (PSI), Switzerland

11:10 I2 **History, Current Status, and Prospect for EUVL**

Takeo Watanabe (渡邊 健夫), Univ. of Hyogo, Japan

11:40 I3 **Enhanced Edge Etching Resistance and EUV-lithographic Performance of a Tin-oxide Photoresist Via a Blend Strategy**

Rai-Shung Liu (劉瑞雄), National Tsing Hua Univ. (國立清華大學)

12:10 Lunch

Session Chair: Mau-Tsu Tang (湯茂竹)

13:30 I4 **Advancements in Turnkey Attosecond Sources for Extreme Ultraviolet Metrology**

Ming-Chang Chen (陳明彰), National Tsing Hua Univ. (國立清華大學)

14:00 I5 **Study the Optical properties of Structured Materials for Vital Issues in Extreme ultraviolet (EUV) Lithography**

Hsuen-Li Chen (陳學禮), National Taiwan Univ. (國立臺灣大學)

14:30 I6 **Detectors Array for On-Wafer EUV Imaging in Advanced Lithography Systems**

Ya-Chin King (金雅琴), National Tsing Hua Univ. (國立清華大學)

15:00 Coffee Break

Session Chair: Pin-Jiun Wu (吳品鈞)

15:20 I7 **Applications of Atomic Layer Deposition in Extreme Ultraviolet Lithography**

Wen-Hao Cho (卓文浩), National Center for Instrumentation Research (國家儀器科技研究中心)

15:50 I8 **Spectral Responsivity Calibration for EUV Dose Evaluation**

Yi-Chen Chuang (莊宜蓁), Industrial Technology Research Institute (工業技術研究院)

16:20 **Discussion & Closing Remarks**

Except for international speakers, all presentations by domestic speakers will primarily be delivered in Chinese, with English used as a supplement.